Special Issue

Nanoscale Lithography—Pressing Miniaturization towards Ever Smaller Sizes

Message from the Guest Editor

Innovative research has expanded the limits of nanofabrication to ever-smaller size scales, approaching the molecular level. Nanolithography encompasses the tools required to prepare surface structures with well-defined geometries and composition. Nanoscale lithography can be employed to control the arrangement of nanomaterials, biomolecules and organic films and offers unprecedented control for potential device applications, such as sensors, memory storage and molecular electronics. This Special Issue will showcase contributions that present advancements in nanolithography, such as approaches using scanning-probe-based lithography, photolithography, colloidal lithography or ion etching. Correspondingly, nanolithography can disclose detailed information at the smallest of size scales to facilitate studies of the chemistry and associated properties of materials. In addition, the size and composition of nanofabricated patterns can be used to tailor the optical, magnetic and electronic properties of materials for material design. We welcome the submission of research articles and reviews that describe protocols and studies performed using nanoscale lithography.

Guest Editor

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